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<b>AMENDMENT TRANSMITTAL LETTER</b>				Docket No. SON-2769	
Application No. 10/603,689-Conf. #2872		Filing Date June 26, 2003		Examiner D. C. Davis	
Art Unit 1756					
Applicant(s): Hidetoshi Ohnuma					
Invention: EXPOSURE METHOD, MASK FABRICATION METHOD, FABRICATION METHOD OF SEMICONDUCTOR DEVICE AND EXPOSURE APPARATUS					
<b>TO THE COMMISSIONER FOR PATENTS</b>  Transmitted herewith is an amendment in the above-identified application. The fee has been calculated and is transmitted as shown below.					
<b>CLAIMS AS AMENDED</b>					
	Claims Remaining After Amendment	Highest Number Previously Paid	Number Extra Claims Present	Rate	
<b>Total Claims</b>	12	- 20 =	0	x 50.00	0.00
<b>Independent Claims</b>	1	- 3 =	0	x 200.00	0.00
Multiple Dependent Claims (check if applicable) <input type="checkbox"/>					
Other fee (please specify):					
<b>TOTAL ADDITIONAL FEE FOR THIS AMENDMENT:</b>					0.00
<div style="display: flex; justify-content: space-between;"><div><input checked="" type="checkbox"/> Large Entity</div><div><input type="checkbox"/> Small Entity</div></div> <div><input checked="" type="checkbox"/> No additional fee is required for this amendment.</div> <div><input type="checkbox"/> Please charge Deposit Account No. _____ in the amount of \$ _____. A duplicate copy of this sheet is enclosed.</div> <div><input type="checkbox"/> A check in the amount of \$ _____ to cover the filing fee is enclosed.</div> <div><input type="checkbox"/> Payment by credit card. Form PTO-2038 is attached.</div> <div><input checked="" type="checkbox"/> The Director is hereby authorized to charge and credit Deposit Account No. <u>18-0013</u> as described below. A duplicate copy of this sheet is enclosed.</div> <div><input checked="" type="checkbox"/> Credit any overpayment.</div> <div><input checked="" type="checkbox"/> Charge any additional filing or application processing fees required under 37 CFR 1.16 and 1.17.</div>					
Ronald P. Kananen Attorney/Agent Reg. No. 24,104  RADER, FISCHMAN & GRAUER PLLC 1233 20th Street, N.W. Suite 501 Washington, DC 20036 (202) 955-3750				Dated: <u>August 9, 2007</u>	



Docket No.: SON-2769  
(PATENT)

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Patent Application of:  
Hidetoshi Ohnuma

Application No.: 10/603,689

Confirmation No.: 2872

Filed: June 26, 2003

Art Unit: 1756

For: EXPOSURE METHOD, MASK  
FABRICATION METHOD, FABRICATION  
METHOD OF SEMICONDUCTOR DEVICE  
AND EXPOSURE APPARATUS

Examiner: D. C. Davis

**AMENDMENT AFTER FINAL ACTION UNDER 37 C.F.R. 1.116**

MS AF  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

**INTRODUCTORY COMMENTS**

In response to the Office Action dated July 11, 2007, please amend the above-identified U.S. patent application as follows:

**Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this paper.

**Remarks/Arguments** begin on page 15 of this paper.